



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q62650

Toshiaki AOAI, et al.

Appln. No.: 09/759,362

Group Art Unit: 1752

Confirmation No.: 1920

Examiner: J. CHU

Filed: January 16, 2001

For: ELECTRON BEAM OR X-RAY NEGATIVE-WORKING RESIST  
COMPOSITION

**AMENDMENT UNDER 37 C.F.R. § 1.111**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This Amendment is submitted in response to the Office Action dated January 30, 2003. A Petition for a one-month extension of time is being concurrently filed, making a response due on or before May 30, 2003. Please amend the above-identified application as follows:

**IN THE CLAIMS:**

Please cancel claims 2, 4 and 5 without prejudice or disclaimer.

Please enter the following amended claim 1:

1 (amended). A negative-working resist composition for electron beams or

X-rays comprising (A) a compound generating an acid and/or radical species by the irradiation of electron beams or X-rays selected from the groups consisting of a

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